

Supporting Information

Subwavelength Si Nanowire Arrays for Self-Cleaning Antireflection Coatings

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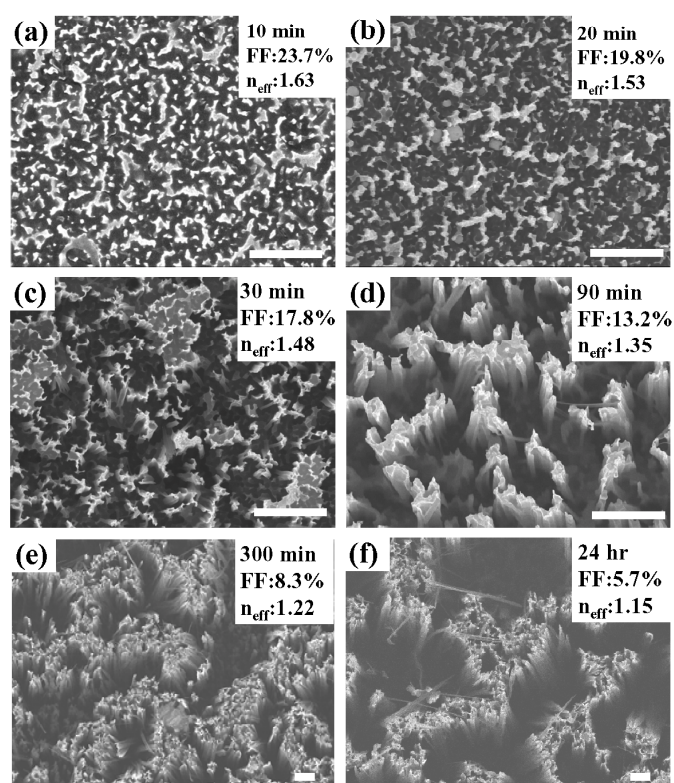


Fig. S1 The plane-view SEM images of Si NWAs with different etching times. FF and N_{eff} are corresponding fill factors and effective indexes of refraction at the air/Si NWA interface. The scale bar is 1 μm .

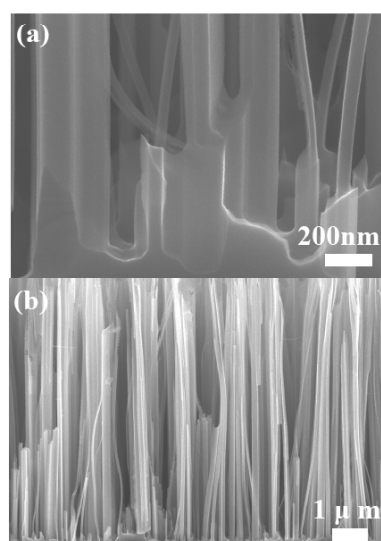


Fig. S2 The SEM images of Si NWAs etched for 5 hr showing (a) two or more NWs merged into a thicker one in the bottom regions of NWA layers, and (b) short NWs with different lengths in the regions close to the bottom.